

Andreas Wucher

List of Publications by Year in descending order

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130
papers

3,099
citations

126708

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docs citations

133
times ranked

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#	ARTICLE	IF	CITATIONS
19	Ionization Probability in Molecular Secondary Ion Mass Spectrometry: Protonation Efficiency of Sputtered Guanine Molecules Studied by Laser Postionization. <i>Journal of Physical Chemistry C</i> , 2017, 121, 8931-8937.	1.5	19
20	Effect of SIMS ionization probability on depth resolution for organic/inorganic interfaces. <i>Surface and Interface Analysis</i> , 2017, 49, 933-939.	0.8	3
21	Reducing the Matrix Effect in Molecular Secondary Ion Mass Spectrometry by Laser Post-Ionization. <i>Journal of Physical Chemistry C</i> , 2017, 121, 19705-19715.	1.5	15
22	Reduce the matrix effect in biological tissue imaging using dynamic reactive ionization and gas cluster ion beams. <i>Biointerphases</i> , 2016, 11, 02A320.	0.6	14
23	A new setup for the investigation of swift heavy ion induced particle emission and surface modifications. <i>Review of Scientific Instruments</i> , 2016, 87, 013903.	0.6	18
24	Secondary ion and neutral mass spectrometry with swift heavy ions: Organic molecules. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2016, 34, .	0.6	9
25	Reducing the Matrix Effect in Organic Cluster SIMS Using Dynamic Reactive Ionization. <i>Journal of the American Society for Mass Spectrometry</i> , 2016, 27, 2014-2024.	1.2	17
26	Dynamic Reactive Ionization with Cluster Secondary Ion Mass Spectrometry. <i>Journal of the American Society for Mass Spectrometry</i> , 2016, 27, 285-292.	1.2	18
27	Time-of-flight secondary neutral & ion mass spectrometry using swift heavy ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2015, 365, 482-489.	0.6	4
28	The influence of crater formation for electron excitation processes in cluster induced collision cascades. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2015, 352, 186-189.	0.6	0
29	Molecular Depth Profiling with Argon Gas Cluster Ion Beams. <i>Journal of Physical Chemistry C</i> , 2015, 119, 15316-15324.	1.5	36
30	A hybrid model describing ion induced kinetic electron emission. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2015, 352, 18-21.	0.6	3
31	Measuring Compositions in Organic Depth Profiling: Results from a VAMAS Interlaboratory Study. <i>Journal of Physical Chemistry B</i> , 2015, 119, 10784-10797.	1.2	56
32	Molecular imaging of biological tissue using gas cluster ions. <i>Surface and Interface Analysis</i> , 2014, 46, 115-117.	0.8	13
33	A mixed cluster ion beam to enhance the ionization efficiency in molecular secondary ion mass spectrometry. <i>Rapid Communications in Mass Spectrometry</i> , 2014, 28, 396-400.	0.7	45
34	Strong Field Ionization of $\hat{1}^2$ -Estradiol in the IR: Strategies To Optimize Molecular Postionization in Secondary Neutral Mass Spectrometry. <i>Journal of Physical Chemistry C</i> , 2014, 118, 25534-25544.	1.5	13
35	Formation of Neutral In _m C _n Clusters under C ₆₀ Ion Bombardment of Indium. <i>Journal of Physical Chemistry A</i> , 2014, 118, 8542-8552.	1.1	11
36	Near Infrared (NIR) Strong Field Ionization and Imaging of C ₆₀ Sputtered Molecules: Overcoming Matrix Effects and Improving Sensitivity. <i>Analytical Chemistry</i> , 2014, 86, 8613-8620.	3.2	16

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37	Does local disorder influence secondary ion formation?. Surface and Interface Analysis, 2014, 46, 18-21.	0.8	0
38	Investigations of molecular depth profiling with dual beam sputtering. Surface and Interface Analysis, 2013, 45, 175-177.	0.8	2
39	Ionization probabilities of sputtered indium atoms under atomic and polyatomic Au ⁺ ion bombardment. Surface and Interface Analysis, 2013, 45, 87-89.	0.8	7
40	A statistical interpretation of molecular delta layer depth profiles. Surface and Interface Analysis, 2013, 45, 39-41.	0.8	5
41	An experimental and theoretical view of energetic C ₆₀ cluster bombardment onto molecular solids. Surface and Interface Analysis, 2013, 45, 50-53.	0.8	7
42	The role of electron temperature dynamics for secondary ion formation. Surface and Interface Analysis, 2013, 45, 72-74.	0.8	2
43	Temperature effects of sputtering of Langmuir-Blodgett multilayers. Surface and Interface Analysis, 2013, 45, 65-67.	0.8	2
44	A microscopic view of secondary ion formation. Nuclear Instruments & Methods in Physics Research B, 2013, 303, 108-111.	0.6	10
45	Computer simulation of internal electron emission in ion-bombarded metals. Nuclear Instruments & Methods in Physics Research B, 2013, 303, 55-58.	0.6	3
46	Computer simulation of cluster impact induced electronic excitation of solids. Nuclear Instruments & Methods in Physics Research B, 2013, 303, 51-54.	0.6	2
47	Ionization probability of sputtered indium atoms: Dependence on projectile impact angle. Nuclear Instruments & Methods in Physics Research B, 2013, 317, 130-136.	0.6	5
48	Depth Profiling of Metal Overlayers on Organic Substrates with Cluster SIMS. Analytical Chemistry, 2013, 85, 10565-10572.	3.2	11
49	Cluster Secondary Ion Mass Spectrometry and the Temperature Dependence of Molecular Depth Profiles. Analytical Chemistry, 2012, 84, 3981-3989.	3.2	11
50	Steady-State Statistical Sputtering Model for Extracting Depth Profiles from Molecular Dynamics Simulations of Dynamic SIMS. Journal of Physical Chemistry C, 2012, 116, 1042-1051.	1.5	14
51	A statistical approach to delta layer depth profiling. Surface and Interface Analysis, 2012, 44, 1243-1248.	0.8	7
52	Molecular Depth Profiling of Buried Lipid Bilayers Using C ₆₀ -Secondary Ion Mass Spectrometry. Analytical Chemistry, 2011, 83, 351-358.	3.2	31
53	Investigating the fundamentals of molecular depth profiling using strong-field photoionization of sputtered neutrals. Surface and Interface Analysis, 2011, 43, 45-48.	0.8	9
54	Influence of the polar angle of incidence on secondary ion formation in self-sputtering of silver. Surface and Interface Analysis, 2011, 43, 24-27.	0.8	10

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55	Fundamental studies of molecular depth profiling using organic delta layers as model systems. <i>Surface and Interface Analysis</i> , 2011, 43, 81-83.	0.8	5
56	Depth profiling of anodic tantalum oxide films with gold cluster ions. <i>Surface and Interface Analysis</i> , 2011, 43, 171-174.	0.8	4
57	Ionization effects in molecular depth profiling of trehalose films using buckminsterfullerene (C60) cluster ions. <i>Surface and Interface Analysis</i> , 2011, 43, 99-102.	0.8	5
58	Retrospective sputter depth profiling using 3D mass spectral imaging. <i>Surface and Interface Analysis</i> , 2011, 43, 41-44.	0.8	4
59	Kinetic excitation of metallic solids: Progress towards a microscopic model. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2011, 269, 1655-1660.	0.6	13
60	Internal electron emission in metal-insulator-metal thin film tunnel devices bombarded with keV argon and gold-cluster projectiles. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2011, 269, 972-976.	0.6	6
61	Influence of the projectile charge state on the ionization probability of sputtered particles. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2011, 269, 1306-1309.	0.6	5
62	A molecular dynamics investigation of kinetic electron emission from silver surfaces under varying angle of projectile impact. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2011, 269, 1661-1664.	0.6	5
63	A statistical analysis of the lateral displacement of Si atoms in molecular dynamics simulations of successive bombardment with 20-keV C60 projectiles. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2011, 269, 1591-1594.	0.6	4
64	Molecular sputter depth profiling using carbon cluster beams. <i>Analytical and Bioanalytical Chemistry</i> , 2010, 396, 105-114.	1.9	41
65	Molecular Depth Profiling with Cluster Secondary Ion Mass Spectrometry and Wedges. <i>Analytical Chemistry</i> , 2010, 82, 57-60.	3.2	24
66	Strong-Field Photoionization of Sputtered Neutral Molecules for Molecular Depth Profiling. <i>Journal of Physical Chemistry C</i> , 2010, 114, 5391-5399.	1.5	18
67	Fluence Effects in C60 Cluster Bombardment of Silicon. <i>Journal of Physical Chemistry C</i> , 2010, 114, 5480-5490.	1.5	23
68	Predicting Kinetic Electron Emission in Molecular Dynamics Simulations of Sputtering. <i>Journal of Physical Chemistry C</i> , 2010, 114, 5715-5720.	1.5	15
69	The influence of projectile charge state on ionization probabilities of sputtered atoms. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2009, 267, 646-648.	0.6	2
70	Three-dimensional depth profiling of molecular structures. <i>Analytical and Bioanalytical Chemistry</i> , 2009, 393, 1835-1842.	1.9	42
71	Kinetic excitation of solids induced by energetic particle bombardment: Influence of impact angle. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2009, 267, 601-604.	0.6	5
72	Crystallographic effects in the kinetic excitation of metal surfaces: A computational study. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2009, 267, 598-600.	0.6	4

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73	Molecular depth profiling of trehalose using a C60 cluster ion beam. Applied Surface Science, 2008, 255, 959-961.	3.1	20
74	A simple erosion dynamics model of molecular sputter depth profiling. Surface and Interface Analysis, 2008, 40, 1545-1551.	0.8	30
75	Chemically alternating langmuir-blodgett thin films as a model for molecular depth profiling by mass spectrometry. Journal of the American Society for Mass Spectrometry, 2008, 19, 96-102.	1.2	40
76	Fundamental studies of molecular depth profiling and 3D imaging using Langmuir-Blodgett films as a model. Applied Surface Science, 2008, 255, 816-818.	3.1	14
77	Formation of atomic secondary ions in sputtering. Applied Surface Science, 2008, 255, 1194-1200.	3.1	36
78	Predicting secondary ion formation in molecular dynamics simulations of sputtering. Applied Surface Science, 2008, 255, 813-815.	3.1	17
79	Three-dimensional molecular imaging using mass spectrometry and atomic force microscopy. Applied Surface Science, 2008, 255, 984-986.	3.1	26
80	Depth Resolution During C60+ Profiling of Multilayer Molecular Films. Analytical Chemistry, 2008, 80, 7363-7371.	3.2	49
81	Molecular Depth Profiling Using a C60 Cluster Beam: The Role of Impact Energy. Journal of Physical Chemistry C, 2008, 112, 16550-16555.	1.5	33
82	Energy Deposition during Molecular Depth Profiling Experiments with Cluster Ion Beams. Analytical Chemistry, 2008, 80, 5293-5301.	3.2	55
83	On the internal energy of sputtered clusters. New Journal of Physics, 2008, 10, 103007.	1.2	14
84	Modeling hot-electron generation induced by electron promotion in atomic collision cascades in metals. Physical Review B, 2008, 77, .	1.1	23
85	Potential electron emission induced by multiply charged ions in thin film tunnel junctions. Physical Review B, 2008, 77, .	1.1	25
86	Kinetic electronic excitation of solids by fast-particle bombardment. Physical Review B, 2008, 78, .	1.1	14
87	Photo and particle induced transport of excited carriers in thin film tunnel junctions. Physical Review B, 2007, 76, .	1.1	49
88	Electron promotion and electronic friction in atomic collision cascades. New Journal of Physics, 2007, 9, 38-38.	1.2	41
89	Protocols for Three-Dimensional Molecular Imaging Using Mass Spectrometry. Analytical Chemistry, 2007, 79, 5529-5539.	3.2	103
90	The role of electronic friction of low-energy recoils in atomic collision cascades. Nuclear Instruments & Methods in Physics Research B, 2007, 258, 83-86.	0.6	7

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91	On the role of electronic friction and electron promotion in kinetic excitation of solids. Nuclear Instruments & Methods in Physics Research B, 2007, 255, 281-285.	0.6	8
92	Molecular Depth Profiling with Cluster Ion Beams. Journal of Physical Chemistry B, 2006, 110, 8329-8336.	1.2	179
93	Yields and ionization probabilities of sputtered In particles under atomic and polyatomic Au ^{m+} ion bombardment. Applied Surface Science, 2006, 252, 6474-6477.	3.1	17
94	Molecular secondary ion formation under cluster bombardment: A fundamental review. Applied Surface Science, 2006, 252, 6482-6489.	3.1	125
95	Determination of energy dependent ionization probabilities of sputtered particles. Applied Surface Science, 2006, 252, 6452-6455.	3.1	21
96	Kinetic energy distributions of neutral In and In ₂ sputtered by polyatomic ion bombardment. Applied Surface Science, 2006, 252, 6470-6473.	3.1	12
97	Kinetic excitation of solids: The concept of electronic friction. Nuclear Instruments & Methods in Physics Research B, 2006, 246, 333-339.	0.6	45
98	Self sputtering yields of silver under bombardment with polyatomic projectiles. Nuclear Instruments & Methods in Physics Research B, 2005, 228, 170-175.	0.6	13
99	Electronic excitation in atomic collision cascades. Nuclear Instruments & Methods in Physics Research B, 2005, 228, 325-329.	0.6	22
100	The use of MIM tunnel junctions to investigate kinetic electron excitation in atomic collision cascades. Nuclear Instruments & Methods in Physics Research B, 2005, 230, 608-612.	0.6	10
101	Sputtering of indium using Au projectiles: Transition from linear cascade to spike regime. Physical Review B, 2005, 72, .	1.1	42
102	Low-energy electronic excitation in atomic collision cascades: A nonlinear transport model. Physical Review B, 2005, 72, .	1.1	47
103	Use of C ₆₀ cluster projectiles for sputter depth profiling of polycrystalline metals. Surface and Interface Analysis, 2004, 36, 1367-1372.	0.8	57
104	Computer simulation of low-energy electronic excitations in atomic collision cascades. Nuclear Instruments & Methods in Physics Research B, 2004, 225, 464-477.	0.6	40
105	Sputtering of indium using polyatomic projectiles. Applied Surface Science, 2004, 231-232, 191-195.	3.1	8
106	Sputtering of Ag under C ₆₀ ⁺ and Ga ⁺ projectile bombardment. Applied Surface Science, 2004, 231-232, 64-67.	3.1	27
107	Molecular depth profiling in ice matrices using C ₆₀ projectiles. Applied Surface Science, 2004, 231-232, 68-71.	3.1	23
108	Depth profiling studies of multilayer films with a C ₆₀ ⁺ ion source. Applied Surface Science, 2004, 231-232, 179-182.	3.1	44

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109	C60 molecular depth profiling of a model polymer. Applied Surface Science, 2004, 231-232, 183-185.	3.1	57
110	Depth profiling of polycrystalline multilayers using a Buckminsterfullerene projectile. Applied Physics Letters, 2004, 84, 5177-5179.	1.5	43
111	Depth Profiling of Langmuir-Blodgett Films with a Buckminsterfullerene Probe. Analytical Chemistry, 2004, 76, 6651-6658.	3.2	53
112	Kinetic Electron Excitation in Atomic Collision Cascades. Physical Review Letters, 2004, 93, 137601.	2.9	32
113	Molecular Depth Profiling of Histamine in Ice Using a Buckminsterfullerene Probe. Analytical Chemistry, 2004, 76, 7234-7242.	3.2	86
114	Projectile size effects on cluster formation in sputtering. Nuclear Instruments & Methods in Physics Research B, 2003, 207, 136-144.	0.6	12
115	Ionization probability of atoms and molecules sputtered from a cesium covered silver surface. Applied Surface Science, 2003, 203-204, 48-51.	3.1	12
116	Generation of large indium clusters by sputtering. Physical Review B, 2002, 66, .	1.1	67
117	Self-sputtering of silver using polyatomic projectiles. Nuclear Instruments & Methods in Physics Research B, 2002, 193, 781-786.	0.6	8
118	Formation of sputtered silver clusters under bombardment with SF ₅ ⁺ ions. Nuclear Instruments & Methods in Physics Research B, 2002, 197, 43-48.	0.6	8
119	Self-sputtering of silver by mono- and polyatomic projectiles: A molecular dynamics investigation. Journal of Chemical Physics, 2001, 115, 8643-8654.	1.2	29
120	Formation of large clusters during sputtering of silver. Nuclear Instruments & Methods in Physics Research B, 2000, 164-165, 677-686.	0.6	62
121	Yields and energy distributions of sputtered semiconductor clusters. Nuclear Instruments & Methods in Physics Research B, 1998, 140, 27-38.	0.6	26
122	The formation of clusters during ion induced sputtering of metals. Nuclear Instruments & Methods in Physics Research B, 1996, 115, 581-589.	0.6	82
123	Cluster formation in sputtering: A molecular dynamics study using the MD/MC-corrected effective medium potential. Journal of Chemical Physics, 1996, 105, 5999-6007.	1.2	78
124	Electron impact and single photon ionization cross sections of neutral silver clusters. Zeitschrift für Physik D-Atoms Molecules and Clusters, 1994, 32, 137-144.	1.0	12
125	VUV photoionization of sputtered neutral silver clusters. Nuclear Instruments & Methods in Physics Research B, 1994, 94, 36-46.	0.6	91
126	The mass distribution of sputtered metal clusters. Nuclear Instruments & Methods in Physics Research B, 1993, 83, 73-78.	0.6	53

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127	Sputtered neutral silver clusters up to Ag ₁₈ . Nuclear Instruments & Methods in Physics Research B, 1993, 82, 337-346.	0.6	101
128	Formation of secondary cluster ions during sputtering of silver and copper. Physical Review B, 1991, 43, 14396-14399.	1.1	21
129	Emission energy dependence of ionization probabilities in secondary ion emission from oxygen covered Ta, Nb and Cu surfaces. Surface Science, 1988, 199, 567-578.	0.8	47
130	Quantitative analysis of thin oxide layers on tantalum by sputtered neutral mass spectrometry (SNMS). Applications of Surface Science, 1982, 10, 342-348.	1.0	23